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PATENT NUMBER

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U.S. UTILITY Patent Application

O.I.P.E. PATENT DATE

SCANNED Q.A. LA

APPLICATION NO. CONT/PRIOR CLASS SUBCLASS ART UNIT EXAMINER
09/945316 430 30 1756 400 ng

Ulrich Boettiger Scott Light

Method <del>and apparatus</del> for controlling radiation beam intensity directed to microlithographic substrates

(as aveiled by Cym TO 2007)

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ORIGINAL						CROSS REFERENCE(S)							
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TERMINAL		DRAWINGS		CLAIMS ALLOWED		
DISCLAIMER	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims 39	Print Claim for O.G	
The term of this patent	(Assistant Examiner). (Date)			NOTICE OF ALLOWANCE MAILED		
subsequent to(date) has been disclaimed.						
The term of this patent shall	Cita	BU.				
not extend beyond the expiration date of U.S Patent. No.	CHRISTOPHER O. YOUNG PRIMARY EXAMINER			ISSUE FEE		
				Amount Due	Date Paid	
	(Primary	Examiner)	(Date)	1600.00		
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